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A B S T R A C T

At a plurality of areas on a mother substrate
(100), array substrate portions (101a to 101f)
including pixel areas (30a to 30f) are formed. At the
5 pixel areas of the array substrate portions, a
plurality of scanning lines and a plurality of signal
lines formed to intersect each other, and pixel
portions are respectively formed close to intersections
of the scanning lines and the signal lines. In an
10 inspecting method for inspecting pixel portions by
using an electron beam tester, with the entire mother
substrate contained in a vacuum chamber, the radiation
range over which beams are radiated in electron beam
scanning by an electron beam scanner is set to a range
15 in which the beam scanning is performed over part of
the array substrate portions (101a to 101f) or it is
performed all over the array substrate portions at the
same time, and inspection information on the pixel
portions of the array substrate portions which are
20 located in the radiation range is acquired.